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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
09/856,402	10/12/2001	Teruyuki Nakano	EHAR0010 9182		
23900 7	7590 11/04/2004		EXAMINER		
J C PATENTS, INC. 4 VENTURE, SUITE 250			CULBERT, ROBERTS P		
IRVINE, CA			ART UNIT PAPER NUMBER		
			1763		
			DATE MAILED: 11/04/2004		

Please find below and/or attached an Office communication concerning this application or proceeding.

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		Application No.	Applicant(s)	3-0
Office Action Summary		09/856,402	NAKANO ET AL.	
		Examiner	Art Unit	
		Roberts Culbert	1763	
Period fe	The MAILING DATE of this communication app or Reply	pears on the cover sheet with the	correspondence addre	ess
THE - External control	MAILING DATE OF THIS COMMUNICATION. Insions of time may be available under the provisions of 37 CFR 1.13 If SIX (6) MONTHS from the mailing date of this communication. If period for reply specified above is less than thirty (30) days, a reply of period for reply is specified above, the maximum statutory period ware to reply within the set or extended period for reply will, by statute, reply received by the Office later than three months after the mailing led patent term adjustment. See 37 CFR 1.704(b).	36(a). In no event, however, may a reply be ti y within the statutory minimum of thirty (30) da vill apply and will expire SIX (6) MONTHS from Cause the application to become ARANDONI	imely filed ys will be considered timely. n the mailing date of this comm	nunication.
Status				
	Responsive to communication(s) filed on <u>16 Sec</u> This action is FINAL . 2b) This Since this application is in condition for allowant closed in accordance with the practice under E	action is non-final. nce except for formal matters, pro		erits is
Disposit	ion of Claims			
5) □ 6) ⊠ 7) □ 8) □ Applicati 9) □ 10) ⊠	Claim(s) 1-10 is/are pending in the application. 4a) Of the above claim(s) is/are withdraw Claim(s) is/are allowed. Claim(s) 1-10 is/are rejected. Claim(s) is/are objected to. Claim(s) is/are objected to. Claim(s) are subject to restriction and/or on Papers The specification is objected to by the Examiner The drawing(s) filed on 12 October 2001 is/are: Applicant may not request that any objection to the discussion of the	election requirement. a)⊠ accepted or b)⊡ objected lrawing(s) be held in abeyance. Seconds is required if the drawing(s) is objected the drawing(s) is objected.	e 37 CFR 1.85(a). jected to. See 37 CFR 1	121(d). 152
	inder 35 U.S.C. § 119			
12)⊠ <i>a</i>)[Acknowledgment is made of a claim for foreign p All b) □ Some * c) □ None of: 1. □ Certified copies of the priority documents 2. □ Certified copies of the priority documents 3. □ Copies of the certified copies of the priority application from the International Bureau ee the attached detailed Office action for a list of	have been received. have been received in Application ty documents have been received (PCT Rule 17.2(a)).	on No ed in this National Stag	ge
attachment	(s)			
)	e of References Cited (PTO-892) e of Draftsperson's Patent Drawing Review (PTO-948) nation Disclosure Statement(s) (PTO-1449 or PTO/SB/08) No(s)/Mail Date	4) Interview Summary (Paper No(s)/Mail Da 5) Notice of Informal Pa 6) Other:	(PTO-413) te atent Application (PTO-152)

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DETAILED ACTION

Response to Arguments

Applicant's arguments filed 9/16/04 have been fully considered but they are not persuasive.

Applicant as argued that Dryer fails to teach, "maintaining a prescribed gap from a periphery of said semiconductor wafer" as claimed by applicant.

The argument is not persuasive for two reasons. First, although Dryer states that "the wafer edges are in contact with pad 15a" as pointed out by applicant, Dryer also clearly illustrates that a small prescribed gap is maintained between the pad and the periphery of the wafer in Figure 4, and further, that a gap is maintained between the pad and the periphery of the wafer in Figure 5. Second, since a slurry (comprising a chemical solution with abrasive silica particles) is disposed between the pad and the periphery of the wafer, there must be a small gap between the pad and the wafer where the slurry resides.

Applicant as argued that Dryer fails to teach "wherein said polishing solution is drawn into said gap between the peripheral edge of said semiconductor wafer and said rotary body to conduct non-contact polishing of the peripheral edge of said semiconductor wafer."

The argument is not persuasive because as seen in figures 4 and 5 of Dryer, a small gap exists between the polishing pad and the wafer periphery as claimed by applicant. Since Dryer teaches that chemical-mechanical polishing slurry is disposed in the grooves (16) of the polishing pad, the slurry is disposed in the small gaps illustrated in figures 4 and 5 and also in a gap (occupied by the slurry) between the polishing pad and the wafer.

Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

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Claims 1, 3 and 4 are rejected under 35 U.S.C. 102(b) as being anticipated by U.S. Patent 5,128,281 to Dryer et al.

Regarding Claim 1, Dryer teaches a rotary mechanism (clamping plates 12) holding a wafer 10 while rotating it in a prescribed direction. A rotary body (roller 15) rotates relative to the semiconductor wafer while maintaining a gap (Figs. 4 and 5) from the periphery of the wafer. See Fig. 1. A polishing solution channel holes (20) and polishing solution supply portion (dispenser 19) are also provided.

Regarding claim 31, the rotary mechanism holds a plurality of semiconductor wafers is a stacked state, according to the illtlstration of Fig. 1 and col. 2, line 29.

Regarding claim 4, Dynamic pressure generating grooves 16 are formed on the peripheral surface of the rotary body facing the periphery of the wafer.

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

This application currently names joint inventors. In considering patentability of the claims under 35 U.S.C. 103(a), the examiner presumes that the subject matter of the various claims was commonly owned at the time any inventions covered therein were made absent any evidence to the contrary. Applicant is advised of the obligation under 37 CFR 1.56 to point out the inventor and invention dates of each claim that was not commonly owned at the time a later invention was made in order for the examiner to consider the applicability of 35 U.S.C. 103(c) and potential 35 U.S.C. 102(e), (f) or (g) prior art under 35 U.S.C. 103(a).

Claims 2, 7, and 8 are rejected under 35 U.S.C. 103(a) as being unpatentable over U.S. Patent 5,128,281 to Dryer in view of U.S. Patent 6,280,294 to Miyamoto.

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The teachings of Dryer were discussed above.

Dryer fails to teach a polishing solution tank and a polishing solution circulation portion.

Miyamoto teaches in col. 5 lines 35-44 that the substrates are polishing as they are immersed in an abrasive liquid 3 and that an abrasive liquid flowing hole 23 is provided to circulate the liquid. Miyamoto teaches that that the immersion while polishing method ensures a high precision, high-efficiency polishing result without damaging the polishing surface as the immersion provides a buffer for the wafers.

Thus, it would have been obvious for one of ordinary skill in the art at the time of the claimed invention to provide a polishing solution tank and a polishing solution circulation portion.

Claims 5, 6, 9, and 10 are rejected under 35 U.S.C. 103(a) as being unpatentable over Dryer in view of Miyamuto as applied to claims 2, 7, and 8 above, and further in view of U.S. Patent 4,426,151 to Aguro et al. and U.S. Patent 5,076,026 to Mizuguchi et al.

The teachings of Dryer and Miyamuto were discussed above.

Regarding claims 5 and 9, neither Dryer nor Miyamuto teaches a magnet installed in the rotary body and a magnetic polishing solution. Agure teaches a magnet installed in rotary body (magnet roller 12). The motivation to provide a magnet installed in the rotary body is to enhance the polishing effect by introducing s magnetic fluid density to the polishing environment.

Aguro fails to teach a magnetic polishing solution. Mizuguchi teaches a magnetic polishing fluid in col. 7, lines 31-36. In col. 3, lines 15-21, Mizuguchi teaches that the use of the magnetic polishing fluid provides a magnetic field and introduces a source of vibration to micro-grind the workpiece. Thus, it would have been obvious for one of ordinary skill in the art at the time of the claimed invention to provide a magnet and magnetic polishing fluid in the polishing apparatus resulting from the combined teachings of Dryer and Miyamuto.

Regarding claims 6 and 10, neither Dryer nor Miyamuto teach that the rotary body is formed of an elastic material. According to the specification page 21 of this present invention such elastic materials that comprise hardness between 7 and 40 Hs include synthetic resin. Aguro teaches in col. 5, lines 50-54 that the material of construction for the scraper member is a synthetic resin. Though Aguro does not

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specifically teach that the roller is also made of synthetic resin one of ordinary skill in the art at the time of the claimed invention would have chosen synthetic resin as it a suitable material of construction with the desired chemical and physical properties needed for the processing environment.

Conclusion

Applicant's amendment necessitated the new ground(s) of rejection presented in this Office action. Accordingly, **THIS ACTION IS MADE FINAL**. See MPEP § 706.07(a). Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the date of this final action.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Roberts Culbert whose telephone number is (571) 272-1433. The examiner can normally be reached on Monday-Friday (7:30-4:00).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Gregory Mills can be reached on (571) 272-1439. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

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R. Culbert A. Culhert

P. Hassanzadel primary Examiner AU 1763